Evaluation of analytical instrumentation

Part XXIV. Instrumentation for quadrupole inductively coupled plasma mass spectrometry

Received 14th June 2010, Accepted 14th June 2010
DOI: 10.1039/c005443g

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Introduction

-C A C, G f (C), C. B , J. H , K. E. J. , G. L , J. J. J. E. J. K. E. J. I C -C .A .I .I .I C .I I -C -

H ,

C 1.
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C 3. -C

Notes on the use of this document

F
I G 9000

Other reports

A C
:
I. A , *A a. P c.*, 1984, **21**, 4 . *A a* 1998, **123**. 1407.
II. A , *A a. P c.*, 198 , **22**, 128. *A a* 1998, **123**, 141 .
III. IC , *A a. P c.*, 1986, **23**, 109.
I . IC , *A a. P c.*, 1987, **24**, 3.
. I , *A a. P c.*, 1987, **24**, 266.
I. , *A a. P c.*, 1990, **27**, 324.
II. , *A a. P c.*, 1991, **28**, 312.
III. I , *A a. P c.*, 1993, **30**, 296.
I . I , *A a* 1997, **122**, 387.
. I , *A a* 1997, **122**, 393.
I. I , *A a* 1998, **123**, 1649.
II. I , *A a* 2000, **125**, 361.
III. I - I I , *A a* 2000, **125**, 367.
I . I F , *A a* 2000, **125**, 37 .
. I G , *A a* 2001, **126**, 9 3.
I. Б , *Acc ed. Q a. A* ., 2006, **11**, 130.
II. I , *Acc ed. Q a. A* ., 200 , **10**, 1 .
III. , *Acc ed. Q a. A* ., 200 , **10**, 160.
I . CH , *Acc ed. Q a. A* ., 2006, **11**, 69.
. I , *Acc ed. Q a. A* ., 2006, **11**, 610.
I. I , *Acc ed. Q a. A* ., 2006, **11**, 236.
II. I , *Acc ed. Q a. A* ., 2007, **12**, 3.
III. F , *Acc ed. Q a. A* ., 2008, **13**, 4 3.

An overview of inductively coupled plasma mass spectrometry (ICP-MS)

Introduction

I (IC -), IC
A
A (IC) . A
IC -

Key features

IC -

(*Cont'd.*)

AA	$L^{\square 1}$ μ $L^{\square 1}$	. L	
F	μ $L^{\square 1}$	. L	

* : $L^{\square 1}$ ¼ 1 10^{12}, $L^{\square 1}$ ¼ 1 10^{9}, μ $L^{\square 1}$ ¼ 1 10^{6}.

F	I
L	
(a) Previous instruments	
( ) I	C I IC -
( )	C I
( ) & ( )	F H I . I
( ) C f	C f I f
(b) Servicing	( ) :
( )	A D I E
( ) A	I
( ) E	I A
(c) Technical support	( ) : I ( )/I
( ) A	
( )	
( )	I
( )	I A
( ) &	

(*Cont'd.*)

F	I
I	
1. High frequency (HF) generators	27 H A
(*a*)	( ). IC - HF
(*b*)	A HF I I

(*Cont'd.*)

F		I
( ) C	f	

(C ...d.)

F		I	
C			

(

(*Continued*)

(*c*)		
5. Interface		
(*a*)		
(*b*)		
(*c*)		
(*d*)		
(*e*)		
6. Vacuum system		
7. Ion detector		
(*a*)		

(*Contd.*)

(*Continued*)

F	I

8. Instrument control and monitoring

(*a*) I

(*Cont'd.*)

(*d*)		

(*Cont'd.*)